

Amendments to the Claims

The claims have been amended as follows. Underlines indicate insertions and ~~strikeouts~~ indicate deletions.

105. (Currently amended) A method of forming a an insulative material adjacent a conductive electrical component comprising:

providing a ~~mass~~ an initial material adjacent the conductive electrical component, the ~~mass~~ initial material comprising pores having a size and the ~~mass~~ comprising molecules consisting of silicon and carbon;

forming a layer overlying the mass; and

decreasing the dielectric constant of the initial material to form the insulative material by vaporizing a portion of the initial material ~~mass~~ to expand the size of the pores ~~within the mass~~.

111. (Currently amended) The method of Claim 105, further comprising forming a layer over the initial material ~~mass~~ before the vaporizing.

112. (Currently amended) The method of Claim 105, further comprising forming a layer over the initial material ~~mass~~ after the vaporizing.

113. (Previously presented) The method of Claim 105, where the conductive electrical component comprises a pair of conductive lines.

114. (Previously presented) The method of Claim 113, further comprising forming at least one support member between the pair of conductive lines.

130. (Currently amended) The method of claim 105 wherein the initial material mass comprises SiC_x .